

Call for papers

IC-PLANTS 2011

The 4th International Conference on Plasma-Nanotechnology & Science

March 10-12, 2011

Takayama public cultural hall, Takayama-city, Gifu, JAPAN

Sponsored by - Plasma Nanotechnology Research Center (PLANT), Nagoya University
Co-sponsored by - International Training Program, Japan Society for the Promotion of Science
- Aichi Science & Technology Foundation (Tokai Region Knowledge Cluster Headquarters)

In conjunction with - Tokai division of the Japan Society of Applied Physics
- Tokai Branch of the Institute of Electrical Engineers of Japan
- Plasma Electronics Division, Japan Society of Applied Physics
- Plasma Center for Industrial Applications, Nagoya Urban Industrial Promotion Corporation
- The Surface Science Society of Japan
- Japan Vacuum Industry Association

Plasma processing technologies are the state of the art technologies leading the way through ultra-high performance in Nano-materials, microelectronic devices, flat panels, etc. IC-PLANTS is organized for offer an opportunity for discussions and exchange of recent progress of Plasma Science and Nanotechnology among the Plasma COEs in the world. It is absolutely necessary to collaborate between the research communities for clearing the complex issues in the interdisciplinary research fields. 4th IC-PLANTS is to be held in Takayama public cultural hall, Takayama-city, Gifu-prefecture, Japan. The Organizing Committee invites you to the conference and welcomes the submission of your papers.

General Topics

Theme: “Fundamentals of plasma processes”, “Atmospheric pressure plasma”, “Plasma biotechnology”

Topics: Nano-fabrication, Diagnostics and monitoring of plasmas and Reaction surfaces, Nano-electronics, Nano-biology, Interdisciplinary or integrated research with Plasma technologies, Nano-optics, MEMS/NEMS technologies, Process technologies for flat panel display, Environmental technologies, Equipment technologies, Emerging new concept

Invited speakers

Zoran Lj. Petrović (Institute of Physics, Serbia), Klaus Bartschat (Drake University, USA), Michael Kong (Loughborough University, UK), Rod Boswell (The Australian National University, Australia), Pascal Chabert (LPP Ecole Polytechnique, France), William G. Graham (Queen’s University Belfast, UK), Jüergen Roepke (Institute of low temperature plasma physics, Germany), Seiichi Miyazaki (Nagoya University, Japan), Toshiro Kaneko (Tohoku University, Japan)

Submission of Abstracts (Oral and Poster Sessions)

Abstract (A4 size, less than two pages) should be submitted by **January 19, 2011** via the web.

Abstract submission (<http://www.plasma.engg.nagoya-u.ac.jp/IC-2011/>) will be opened by the middle of December, 2010.

Registration Fee Early (by February 28, 2011) : General : ¥10,000.-, Student : *Free*
On-site : General : ¥15,000.-, Student : *Free*

Organizing Committee Chair

Hiroataka Toyoda, Professor, Plasma Nanotechnology Research Center, Nagoya University
Masaharu Shiratani, Co-chair, Professor, Kyushu University

Conatct *Hiroki Kondo* (Executive Committee Chair), Associate Professor, Nagoya University
e-mail : ic-plants@plasma.engg.nagoya-u.ac.jp

<http://www.plasma.engg.nagoya-u.ac.jp/IC-2011/>